

Form 1449 (Modified)

Information Disclosure
Statement By Applicant

(Use Several Sheets if Necessary)

Atty Docket No.

LAM1P124D1

Application No.:

Not Yet Assigned

Applicant

Bailey III et al.

Filing Date

Herewith

Art Group Unit

Unknown

Page 1 of 1

 10/30/01
 09/94806
 U.S. PTO

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A.	4,690,793	09/1987	"Hitachi, Ltd. et al."			
	B.	4,948,458	08/1990	Ogle			
	C.	4,990,229	02/1991	Campbell et al.			
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	K.	5,788,799	08/1998	Steger et al.			
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Foreign Patent or Published Foreign Patent Application

Examiner Initial		Document No.	Publication Date	Country or Patent Office	Class	Sub-Class	Translation	
							Yes	No
	O.	0 819 780 A2	01/1998	EPO				
	P.	0 837 489 A2	04/1998	EPO				
	Q.	0 838 842 A2	04/1998	EPO				
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	T.	Y. Fujiwara et al., "Temperature control of plasma grid for continuous operation in cesium-seeded volume negative ion source," Rev. Sci. Inst. 69 (2), 2.98, pp. 1173-1175.
	U.	Mizuhara et al., "Ceramic/Metal Seals," Engineering Materials Handbook, 11.95, pp. 502-210.
	V.	D.R. Write et al., "Low temperature etch chuck: Modeling and experimental results of heat transfer and wafer temperature," J. Vac. Sci. Technol. A 10 (4), 7.92, pp. 1065-1070.
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	Date Considered	04/03/02

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered.
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Patent Office

DEC 12 2001

Attorney Docket No. LAM1P124D1

Application No.: 09/943,806

Applicant: BAILEY III et al.

Filing Date: 08/30/2001

Group: 1763

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↓	A.	5,707,452	01/1998	Dandl			
	B.	5,795,451	08/1998	Tan et al.			
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	F.						

Foreign Patent or Published Foreign Patent Application								
Examiner Initial		Document No.	Publication Date	Country or Patent Office	Class	Sub-Class	Translation	
							Yes	No
	G.							
	H.							
	I.							

Other Documents		
Examiner Initial	No.	Author, Title, Place (e.g. Journal) of Publication, Date
	J.	
	K.	
	L.	
	M.	
	N.	
	O.	
	P.	
	Q.	
Examiner	Date Considered	

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